

REMARKS

Claims 1, 5, 6, 10, 11, 15, 16 and 20 are amended. Claims 2, 3, 7, 8, 12, 13, 17 and 18 are cancelled. Claims 65-74 are added. Claims 1, 4-6, 9-11, 14-16, 19, 20 and 65-74 are in the application for consideration.

Each of the independent claims is amended to recite that the etchant gas composition includes C_4F_6 . Support for the same is inherent in Applicant's application as-filed, for example at p.2, ln.5.

The applied and other cited references have been carefully reviewed. None is seen to disclose the use of C_4F_6 . Accordingly, none of the references can be considered as anticipating Applicant's amended claims 1, 6, 11 and 16. As not one of the cited references is seen to disclose an etchant gas composition comprising C_4F_6 , it is inconceivable that the references, whether taken alone or in combination, could suggest Applicant's various claims 1, 6, 11 and 16 claim combinations. Accordingly, Applicant's independent claims as presented herein should be allowed, and action to that end is requested.

Dependent claims 65-74 are added and are clearly supported by the specification, for example, at p.11, lns.5-11.

Applicant's rejected dependent claims should be allowed as depending from allowable base claims, and for their own recited features which are neither shown nor suggested in the cited art. Action to that end is requested.

This application is believed to be in immediate condition for allowance, and action to that end is requested.

Respectfully submitted,

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By: 

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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application Serial No. 09/945,508
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 Inventorship Kei-Yu Ko
 Assignee Micron Technology, Inc.
 Group Art Unit 1765
 Examiner Lynette T. Umez Eronini
 Attorney's Docket No. MI22-2037
 Title: Etchant Gas Composition (as Amended)

VERSION WITH MARKINGS TO SHOW CHANGES MADE
ACCOMPANYING RESPONSE TO JUNE 4, 2002 OFFICE ACTION

In the Claims

The claims have been amended as follows. Underlines indicate insertions and ~~strikeouts~~ indicate deletions.

1. (Amended) An etchant gas composition, comprising:
 - a carrier gas;
 - ~~one or more C₂F₆ gases~~ C₄F₆;
 - CH₂F₂; and
 - a gas selected from the group consisting of CHF₃, CF₄, and mixtures thereof.

Claims 2 and 3 are cancelled.

5. (Amended) The etchant gas composition according to Claim 1, wherein the carrier gas ~~is~~ comprises argon.

6. (Amended) An etchant gas composition, consisting essentially of:
a carrier gas;
~~one or more C₂F₆ gases~~ C₄F₆;
CH₂F₂; and
CHF₃.

Claims 7 and 8 are cancelled.

10. (Amended) The etchant gas composition according to Claim 6,
wherein the carrier gas ~~is~~ comprises argon.

11. (Amended) An etchant gas composition, consisting essentially of:
a carrier gas;
~~one or more C₂F₆ gases~~ C₄F₆;
CH₂F₂; and
CF₄.

Claims 12 and 13 are cancelled.

15. (Amended) The etchant gas composition according to Claim 11,
wherein the carrier gas ~~is~~ comprises argon.

16. (Amended) An etchant gas composition, consisting essentially of:
a carrier gas;
~~one or more C₂F₆ gases~~ C₄F₆;
CH₂F₂;
CHF₃; and
CF₄.

Claims 17 and 18 are cancelled.

20. (Amended) The etchant gas composition according to Claim 16,
wherein the carrier gas ~~is~~ comprises argon.

New claims 65-74 are added.

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